

Minutes from OpenPICs WP 3 meeting 02-10-2017

Present: Weiming (chairing), Rui, Roel, Rob, Huub, Rene, Tjibbe, Robert

Time: 13:30-14:30

Discussion/action points

Nr.	Description	Responsible
1.	Al-MQW Design Quantum well design will be fixed by CW43	Weiming
2.	Zn Diffusion Rene will perform experiment no. 2 starting CW42 to analyze influence of mask opening ratio and to acquire more time-resolved data. Ask for SIMS measurement quotation.	Rene
3.	Thick RF Insulation BCB adhesion is now given due to utilization of SiO ₂ adhesion layer. Metallization using appropriate mask is planned to determine RF line performance. Different metallization types as well.	Tjibbe
4.	Etching Optimization Further analysis of CH ₄ -H ₂ based recipe in Smart's cleanroom on actual wafers required due to surface roughness issues. CH ₄ -H ₂ -Cl ₂ based recipe work is continued in Smart's cleanroom as well.	Rui Roel
5.	Stepper Lithography Continued work on MaN resist development. First exposures have been performed. Proceed with FE mapping.	Robert

Next meeting is 16th October, 2017, 14:00